

Title (en)

METHOD AND DEVICE FOR CONTROLLING THE MANUFACTURE OF SEMICONDUCTOR BY MEASURING CONTAMINATION

Title (de)

VERFAHREN UND VORRICHTUNG ZUR KONTROLLE DER HERSTELLUNG VON HALBLEITLERN MITTELS KONTAMINATIONSMESSUNG

Title (fr)

PROCEDE ET DISPOSITIF DE PILOTAGE DE FABRICATION DE SEMI-CONDUCTEURS PAR MESURE DE CONTAMINATION

Publication

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Application

EP 10798766 A 20101216

Priority

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Abstract (en)

[origin: WO2011073348A1] The present invention relates to a device for handling substrates in a semiconductor manufacturing plant that has substrate processing facilities, a substrate storage means, a substrate transport means, and a system for controlling manufacturing execution systems (MES) in functional relationship to the substrate processing facilities, the substrate storage means, and the substrate transport means. Said device includes: at least one substrate storage and transport box that is transported by the transport means and stored in the storage means; at least one device for analyzing the gases forming the inner atmosphere of a substrate storage and transport box, said analyzing device producing analysis signals that represent the critical gas amount that is capable of generating molecular contamination and is present in the storage and transport box; and a control device that controls the transport means and storage means, the control device including instructions for detecting a need for molecular decontamination on the basis of analysis signals emitted by the gas-analyzing device.

IPC 8 full level

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